

CLAIMS

1. A Co-Cr-Pt-B alloy sputtering target comprising an island-shaped rolled structure formed from a Co-rich phase based on the primary crystal formed upon casting.
2. A Co-Cr-Pt-B alloy sputtering target according to claim 1, wherein the island-shaped rolled structure has an average size of $200\text{ }\mu\text{m}$ or less.
3. A Co-Cr-Pt-B alloy sputtering target according to claim 1 or claim 2, comprising a Co-rich phase and B-rich phase island structure based on the eutectic structure formed upon solidification between the island-shaped structures formed from a Co-rich phase based on the primary crystal.
4. A Co-Cr-Pt-B alloy sputtering target according to any one of claims 1 to 3, wherein the average crystal grain size of the crystal in the Co-rich phase is $50\text{ }\mu\text{m}$ or less.
5. A Co-Cr-Pt-B alloy sputtering target according to any one of claims 1 to 4, comprising a hot rolled structure.
6. A Co-Cr-Pt-B alloy sputtering target according to claim 5, wherein the hot rolling ratio is 15 to 40%.